

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Shigeki KAMBARA, *et al.*

Conf.: 5132

Application No.: 10/519,998

Art Unit: 1752

Filed: January 5, 2005

Examiner: John CHU

For: PHOTORESIST RESIN AND PHOTORESIST
RESIN COMPOSITION

AMENDMENT UNDER 37 CFR 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

Responsive to the Office Action of April 6, 2007, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This response includes:

Amended Claim Set; and

Remarks.